



In re Application of:  
Yim, et al.

Group Art Unit: 1762

Examiner: Marianne L. Padgett

For: Ultra Low Dielectric Materials  
Based on Hybrid System of Linear  
Silicon Precursor and Organic  
Porogen by Plasma-Enhanced  
Chemical Vapor Deposition  
(PECVD)

CERTIFICATE OF MAILING  
37 CFR 1.8

I hereby certify that this correspondence is being deposited on  
6/9, 2005 with the United States Postal Service as  
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Amendment, Commissioner for Patents, P.O. Box 1450,  
Alexandria, VA 22313-1450.

6/9/05                      *[Signature]*  
Date                              Signature

**RESPONSE TO OFFICE ACTION DATED APRIL 14, 2005**

In response to the Office Action dated April 14, 2005, having a shortened statutory period for response set to expire on July 14, 2005, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/7034.P1/KMT for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

**Amendments to the Specification** are listed beginning on page 2 of this paper. **Amendments to the Claims** are reflected in the listing of claims which begins on page 4 of this paper. **Remarks** begin on page 8 of this paper.